

IN THE CLAIMS

Please cancel claims 43 and 44 without prejudice, and amend the claims as follows:

1 to 18. (canceled).

19. (currently amended) A process for producing a rotationally symmetrical quartz glass crucible, said process comprising:

creating an electric arc by means of an electrode arrangement comprising one or several anodes and a cathode so as to heat a wall section of the quartz glass crucible as said quartz glass crucible is rotated about a rotational axis;

creating an additional electric arc heating an additional wall section of the quartz glass crucible by means of at least one additional electrode arrangement comprising one or more anodes and a cathode; and

wherein the electrode arrangements and respective heating zones thereof are spaced from each other in relation to a periphery of the quartz glass crucible; and

wherein the heating of each electrode arrangement is applied for a duration and the duration is dependent upon a rate of rotation of the quartz glass crucible.

20. (previously presented) A process according to Claim 19, wherein the wall sections heated by the electrode arrangements are located at a distance from one another in a direction of the rotational axis of the quartz glass crucible.

21. (canceled)

22. (previously presented) A process according to Claim 19, wherein the electrode arrangements are located in different positions at a distance from one another in a direction of the rotational axis of the quartz glass crucible.

23. (previously presented) A process according to Claim 19, wherein the electrode arrangements are displaceable independently from one another.

24. (previously presented) A process according to Claim 22, wherein the electrode arrangements are displaceable independently from one another.

25. (previously presented) A process according to Claim 19, wherein the electrode arrangements are evenly spaced in relation to the periphery of the quartz glass crucible.

26. (previously presented) A process according to Claim 22, wherein the electrode arrangements are evenly spaced in relation to the periphery of the quartz glass crucible.

27. (previously presented) A process according to Claim 23, wherein the electrode arrangements are evenly spaced in relation to the periphery of the quartz glass crucible.

28. (previously presented) A process according to Claim 24, wherein the electrode arrangements are evenly spaced in relation to the periphery of the quartz glass crucible.

29. (previously presented) A process according to Claim 19 wherein at least one of the electrode arrangements is provided with a supply apparatus and supplies SiO_2 granulate, and at least one of the electrode arrangements provides exclusively heating.

30. (previously presented) A process according to Claim 22 wherein at least one of the electrode arrangements is provided with a supply apparatus and supplies SiO_2 granulate, and at least one of the electrode arrangements provides exclusively heating.

31. (previously presented) A process according to Claim 23 wherein at least one of the electrode arrangements is provided with a supply apparatus and supplies SiO_2 granulate, and at least one of the electrode arrangements provides exclusively heating.

32. (canceled)

33. (canceled)

34. (canceled)

35. (canceled)

36. (canceled)

37. (previously presented) A process according to Claim 19 wherein the additional electrode arrangement is inclined toward a section of the quartz glass crucible opposite the first electrode arrangement.

38. (currently amended) A process for producing a rotationally symmetrical quartz glass crucible, said process comprising:

creating electric arcs by means of a plurality of electrode arrangements each comprising a cathode and one or more anodes and heating in a respective heating zone a wall

of the quartz glass crucible while said quartz glass crucible is rotated about a rotational axis thereof; and

the heating zones of the electrode arrangements being spaced from each other in relation to a periphery of the quartz glass crucible; and

wherein the heating of each electrode arrangement is applied for a duration and the duration is dependent upon a rate of rotation of the quartz glass crucible.

39. (previously presented) A process according to Claim 38, wherein the electrode arrangements are located in different positions at a distance from one another in a direction of the rotational axis of the quartz glass crucible.

40. (previously presented) A process according to Claim 38, wherein the electrode arrangements are displaceable independently of each other.

41. (previously presented) A process according to Claim 38, wherein the heating zones of the electrode arrangements are evenly spaced about the periphery of the quartz glass crucible.

42. (previously presented) A process according to Claim 38 wherein at least one of the plurality of electrode arrangements has a supply apparatus and supplies SiO₂ granulate in addition to heating the wall of the quartz glass crucible, and at least one of the plurality of electrode arrangements does not supply granulate but provides only heating of the wall of the crucible.

43 and 44. (canceled)